IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Takeru WATANABE et al. Conf.:

Appl. No.: NEW Group:

Filed: May 20, 2004 Examiner:

For: BASIC COMPOUND, RESIST COMPOSITION AND

PATTERNING PROCESS

PRELIMINARY AMENDMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

May 20, 2004

Sir:

The following preliminary amendments and remarks are respectfully submitted in connection with the above-identified application.

This amendment includes: Amendments to the Specification; and Remarks.